

The Characterisation and Optimisation of TLC NAND Flash Memory using Machine Learning

A Position Paper

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Abstract: Flash memory is non-volatile and, while it is becoming ever more commonplace, it is not yet a complete replacement for hard disk drives. The physical layout of Flash means that it is more susceptible to degradation over time, leading to a limited lifetime of use. This paper will give an introduction to NAND Flash memory, followed by an overview of the relevant research on the reliability of MLC memory, conducted using Machine Learning (ML). The results obtained will then be used to characterise and optimise the reliability of TLC memory.

1 INTRODUCTION

Up until relatively recently spinning hard disk drives were the most common, permanent, form of data storage. However, this space is now being rapidly filled by NAND Flash memory, with Flash taking more than two-thirds of the total non-volatile silicon memory market (KonceptAnalytics, 2010).

Flash memory is a non-volatile memory, meaning that it does not lose data when the power source is removed. It has a complex memory cell structure, which can be erased by electrical methods (Pavan et al., 1997). It was called Flash because the data could be erased very quickly - in a flash (Aritome et al., 1993).

Important reliability metrics with regards to Flash memory are *endurance* and *retention*. Endurance is a measure of how many program/erase (P/E) cycles a cell can endure before failure (IEEE, 1998). The endurance values vary between device types and also between manufacturers. Common values for Single Level Cell (SLC) can be 100,000, for MLC can be 5,000-10,000, while for TLC it can be as little as 500 P/E cycles.

Retention is a measure of how long a device can retain settings without being refreshed. According to the JEDEC specification (JEDEC, 2011) for Flash, these figures should be 1 year for 100% of the maximum cycle count, and 10 years for 10% of the maximum cycle count. This means that if a Flash device

is cycled to 100% of its maximum P/E cycle count, then it has to keep the data for 1 year, and if it's cycled at only 10%, then it has to keep the data for 10 years.

P/E cycling creates significant endurance and retention problems which cause the eventual wearout of all Flash memory devices (Pavan et al., 1997). The physics of Flash mean that the electrical stress associated with changing state are the most common cause of threshold voltage (V_{th}) disturbances (Compagnoni et al., 2010). The V_{th} of a cell is the gate voltage at which it is turned on, and disturbances can occur due to degradation in the tunnel oxide. Several methods are employed to combat this wearout mechanism, including Wear Leveling and Error Correction Codes (ECCs), all of which are carried out by the Flash memory controller. This controller creates a single error free data stream from multiple NAND devices and hides the complexity of doing so from the user. It is typically comprised of a host interface and a Flash File System (FFS).

Wear Leveling is required because, without it, data may be continually updated in the same location, leaving other locations less-frequently updated, or not used at all. This can lead to specific, frequently updated blocks wearing out prematurely. To prevent this, the usage of all pages must be kept as level as possible. ECCs are used to correct read errors and are executed from the spare area of the memory. There are many types of ECC, but the most well-known are Reed-Solomon and Bose & Ray-Chaudhuri (BCH)

(Michelsoni et al., 1998). ECCs are needed to deal with various issues including noise, V_{th} disturbances, retention, and related errors, while performing read operations. They are used to increase both endurance and retention of the Flash.

This research will focus on characterising and quantifying the reliability of TLC NAND Flash, and is being undertaken as part of wider collaborative research by a group comprised of one industrial and two educational institutions. The rest of this paper is laid out as follows: a background to Flash memory, previous research on NOR and NAND Flash memory using ML, current research on TLC NAND Flash memory, the tool chain developed, current position, future work, and conclusions.

2 BACKGROUND

There are two distinct types of Flash memory - *NOR* and *NAND*. *NOR* provides fast random memory read access and so, is used to store code and parameter data, because it guarantees 100% good bits (Tewksbury and Brewer, 2008). Random access means the memory can be directly addressed and data can be found in any order, anywhere. As shown in Figure 1, each cell is connected to both the bit and source line, facilitating random access. *NAND* is better for applications that need serial read access, whereas *NOR* is better when random read access is required. *NAND* does allow random access but data access is slower than *NOR* (Tewksbury and Brewer, 2008). Random write has been shown to be as fast on raw *NAND* Flash as serial write access, but slower on Solid State Devices (SSDs) (Desnoyers, 2010).

Serial access facilitates data extraction by passing the data through the rest of the cells in the string, which are put into pass mode, by turning all the cells on. This allows access to the required cell. All cells on a Word Line must be read together and form a page of data, as shown in Figure 2. This diagram shows that each bit line is shared by a string of cells, therefore allowing serial access. *NAND* is denser and cheaper than *NOR*, so has taken over for use in data storage, memory cards, mobile phones and SSDs - where the cost per bit is critical. This fact, along with increased demand for smaller devices, has caused the *NAND* Flash market to grow to over \$25 billion in 2011 (Lee, 2011).

Both *NOR* and *NAND* are based on a Floating Gate (FG) technology consisting of a MOS (Metal Oxide Silicon) Field Effect Transistor or MOSFET. The MOS structure has three layers - the Metal layer is the control gate, the Oxide layer holds the floating

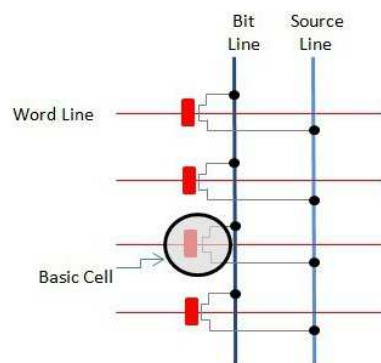


Figure 1: NOR Flash Architecture.

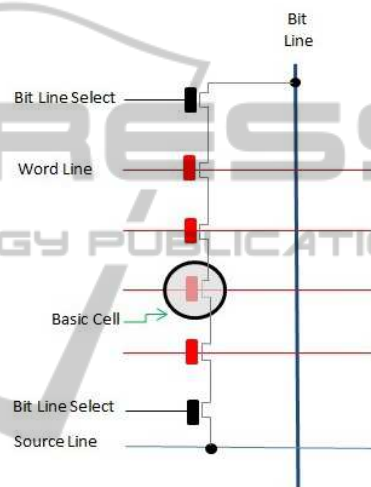


Figure 2: NAND Flash Architecture.

gate, and the Silicon layer.

The floating gate is isolated from the silicon layer by the oxide layer surrounding it. The electrons are tunneled through this oxide layer, as shown in Figure 3. Once a charge is added to the floating gate by a programming operation, it is permanently stored there until an erase operation is performed (Bez et al., 2003) (Hasler and Lande, 2001). The effect of these program and erase operations is to change the V_{th} of the cell.

NOR is programmed by channel-hot-electron (CHE) injection and erased by Fowler-Nordheim (FN) tunneling (Bez et al., 2003). Programming by CHE involves accelerating electrons through the channel between source and drain. These electrons have enough energy to get over the oxide barrier and into the floating gate. Erasing by FN involves applying a high negative voltage to the cell gate with respect to the substrate. This results in the electrons being pulled from the floating gate into the substrate. *NAND* memory uses FN tunneling for programming and erasing. Programming involves applying a high

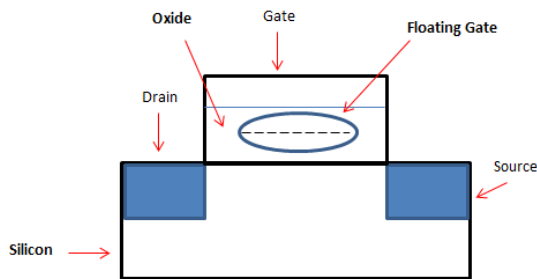


Figure 3: Floating Gate.

positive voltage to the cell gate with respect to the substrate. The electrons are then pulled from the substrate into the floating gate.

Within the NAND Flash family, there are three distinct types of memory. SLC can store only 1 bit of data per cell, and can be either programmed (0) or erased (1), as shown in Figure 4 (a). MLC stores 2 bits of data per cell in 4 levels - 00 Fully Programmed, 01 Partially Programmed, 10 Partially Erased, 11 Fully Erased, as detailed in Figure 4 (b).

Finally, TLC stores 3 bits of data per cell in 8 levels, ranging from 000 Fully Programmed to 111 Fully Erased. The assumed V_{th} distribution arrangements are shown in Figure 4 (c).

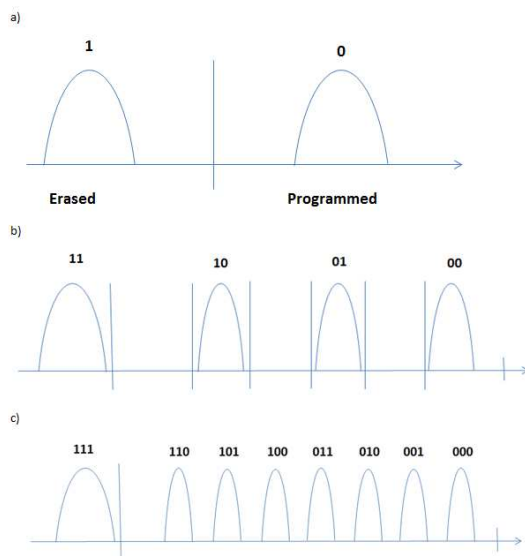


Figure 4: Voltage Threshold Distribution for SLC, MLC and TLC.

3 PREVIOUS RESEARCH

Machine Learning algorithms are algorithms which improve through experience, by evolving behaviours based on empirical data. This research group is us-

ing a family of these algorithms called Evolutionary Algorithms, and two branches in particular - Genetic Algorithms (GAs) and Genetic Programming (GP). These are used for search and optimisation problems. Both techniques are similar, the primary difference being how potential solutions are represented. GA solutions are represented as bit strings, whereas GP solutions are represented as tree structures.

The earliest work on Flash endurance using ML was conducted on NOR memory (Sullivan and Ryan, 2007). In this study, GAs were applied in real time to chips in order to find out if the endurance of Flash memory could be improved by evolving a better set of control parameters. A control group was created by testing a group of cells using factory default values. A single device was used for each run, comprising 7 generations. This work proved that endurance could be extended by up to 3.5 times that of the control group.

A recent discovery (Desnoyers, 2010) found that the latency of read, program and erase operations was lower than the values specified by the manufacturers. Furthermore, due to degradation of the oxide after use, programming speed increased and erase speed decreased. Similar results on programming speed were found by this research group during work carried to characterise NAND. However, it was found that erase time initially decreased sharply, levelled out, then increased. A theory was put forth that this initial decrease was the by-product of an erase algorithm performed on the chip itself. This algorithm would operate similarly to Incremental Step Pulse Programming (ISPP) (Suh et al., 1995), in that a series of erase pulses would be performed to make up an erase operation.

A further finding during the analysis of data was a significant difference in performance between blocks in different locations in a plane, and between pages in a block. Analysis of endurance across pages in a block (Yaakobi et al., 2010) found a difference between MSB and LSB pages. A similar analysis (Cai et al., 2012) was performed with similar results, with the addition of identifying 4 distinct types of pages in each block - a Most Significant Bit (MSB)-even and MSB-odd page, and a Least Significant Bit (LSB)-even and LSB-odd page. Results found by our research group were similar, but performed by analysing all the blocks in a chip, which gave rise to a distinct block-level pattern. Program and erase times were analysed as a function of P/E cycles. We concluded that by using these three values, ML would be able to create a function capable of predicting endurance values for a particular block.

Further research carried out during this time fo-

cused on predicting end-of-life for a NAND Flash part by using start-of-life measurements, such as program and erase time (Hogan et al., 2012a). This study used GP, an extension of GAs (Koza, 1992), to evolve a mathematical function that, given the start-of-life values for read, write and erase times, would predict the useful life of the NAND Flash block. The model obtained up to 95% accuracy on unseen data, thereby proving that it is possible to use this implementation method to predict real endurance figures (Hogan et al., 2012a).

A parallel study to predict retention limits of MLC chips was also carried out using GP (Hogan et al., 2012b). In this work an accelerated test period was developed to test retention, as it takes too long to test retention by waiting for the actual retention period. This involved cycling blocks at high temperature, to replicate normal lifetime usage, followed by a data error count. Next, a specific hexadecimal data pattern was written to the device, after which the device was put into an environmental oven and baked at a high temperature for a period of time. This was calculated using Arrhenius' Equation to be equivalent to 3 months at normal operating temperature. When the bake cycle finished, the data was again read from the device and compared with the data originally written to it. The GP function was then evolved using the number of cycles performed and the number of pre-retention errors as inputs, with the output being the number of post-retention errors. The results from this research showed that it was possible to classify the retention period over 85% of the time.

To date, there have been a number of similar studies on MLC endurance. One of the most relevant demonstrated firstly, that there is a large performance difference between manufacturers, devices and datasheet reliability figures. And, secondly, that there was a difference within blocks when comparing power usage, speed of operations and error rates (Grupp et al., 2009).

4 CURRENT RESEARCH ON TLC

The theory of a TLC memory cell was proposed in 1997 (Tanaka et al., 1997). This new cell would have a reduced capacity area and efficient ECC. In 1995, a method of increasing the density of the NAND Flash cells was proposed (Hemink et al., 1995), using up to 4-level cells. This would require narrow V_{th} distributions and high programming speeds.

It is our contention that TLC will suffer from the same problems with reliability as both SLC (Aritome et al., 1993) and MLC (Grupp et al., 2009), but to

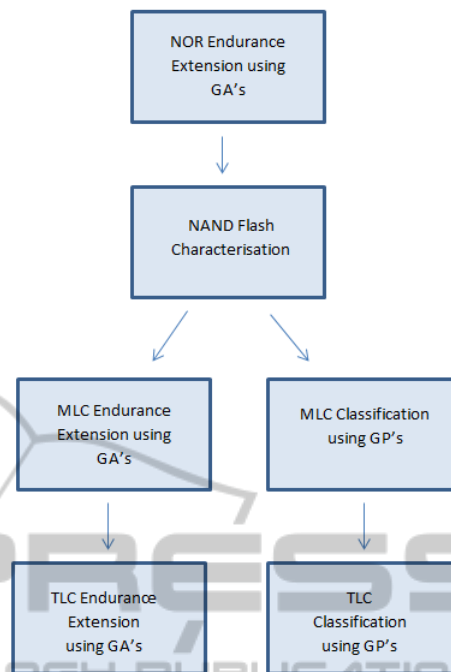


Figure 5: Research Group.

greater degrees. Instead of having two states, programmed or erased, like in SLC, or four states, like in MLC, there are now eight possible states for TLC, as shown in Figure 4 (c), which means there is a far higher chance of V_{th} distributions crossing read boundaries, leading to errors. Because of this, the differences in endurance gradients across blocks and pages in TLC needs to be characterised and quantified.

At the time of writing, there was very little published data or literature on TLC, especially with regards to endurance and retention. This leaves a substantial gap in TLC knowledge which this research will attempt to fill. As well as studying the reliability gradient differences in TLC, a complete block map layout of the specific TLC chips obtained for this project will be laid out. Testing will take into account retention and the permitted Bit Error Rate (BER) for the device as prescribed by the size of the spare area. Also, the method used to perform error mapping across blocks and pages in TLC chips will be investigated. Finally, the results of this work will be incorporated into ML trials that will be run on TLC chips, using the methods refined in the studies by Hogan (Hogan et al., 2012a) and Hogan (Hogan et al., 2012b), to optimise TLC reliability.

A recent relevant study (Yaakobi et al., 2012) mapped the layout of a TLC block and the BER on the level of a block, a page, and a bit, in a selection of individual blocks. This research mapped a TLC page as

having a Left and Right MSB page, a Left and Right Central Significant Bit (CSB), and a Left and Right LSB. To do this, firstly a typical layout of a TLC chip was devised. Next, the BER was analysed, both as an average across a number of blocks, and on individual pages in a block. It was discovered that often the state of the cell in question changed from “the highest level to the lowest level”, rather than one level at a time. A theory proposed to explain this was that the three bits in a TLC chip were not being programmed at the same time, but instead, one at a time. This meant that if an error occurred in either the first or second bit, the state of the cell would be changed by more than one level. Finally, a new ECC was designed, which would work on all three bits simultaneously.

Reliability is a function of both endurance and retention, and while the work mentioned above focused on ECC design, it tested for endurance only, with no attempt at retention testing. Furthermore, only a sample of blocks were trialled and so, no endurance map applicable across devices could be drawn. The proposed work will seek to expand and fill the gaps discussed, by also making use of GP, as described in the previously mentioned MLC studies.

5 THE TOOL CHAIN

The tool chain developed for use in this project is comprised of a NAND Flash Utility Tester, Environmental Oven and Graphical User Interface (GUI).

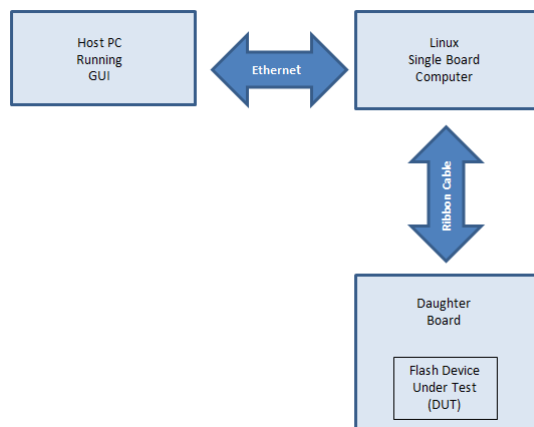


Figure 6: Overview of test system.

As shown in Figure 6, the GUI is installed on a computer, with the tester units connected via Ethernet cables. These, in turn, are connected to daughter boards, on which the Devices Under Test (DUT) are placed. On initialising the GUI a TCP/IP connection to the Linux on the tester unit is opened. A grammar

of commands are then used in order to run program, read and erase operations, among other operations. The Environmental Oven is used to run temperature controlled test cycles - the oven is ported so the tester units can go directly into these ovens.

6 CURRENT POSITION

To date, the research project has completed a number of phases. Firstly, a Non-Disclosure Agreement (NDA) is in place with a manufacturer. This allowed for the receipt of a batch of preproduction TLC Flash part samples and a preliminary datasheet. Following this, an initial set of tests was performed. These tests allowed us to specify a new driver requirement for the existing tester. This will require software and hardware modification to support the new device and this work is currently ongoing.

7 FUTURE WORK

Plans for future work include completing a block map layout of the TLC chip and then comparing it to the one outlined by Yakoobi (Yaakobi et al., 2012). A layout of error mapping across blocks and pages in TLC chips will be completed, with the results then compared to those found by Cai (Cai et al., 2012), when using MLC chips, and Yakoobi (Yaakobi et al., 2012), when using TLC chips from another manufacturer. Following this, ML techniques discussed above will be applied to classify and optimise the TLC chips.

8 CONCLUSIONS

This paper has provided an introduction to Flash memory and an outline of how ML has been shown to improve NOR, and to classify MLC NAND. Current research on TLC NAND has also been introduced, along with a description of this project. We plan to use ML to characterise and optimise reliability of TLC, the results of which will provide important data on TLC memory. This is needed in order to further the understanding of this technology.

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